

## Electronic Supplementary Information (ESI)

### Interface Engineering of 3D BiVO<sub>4</sub>/Fe-Based Layered Double Hydroxide Core/Shell Nanostructures for Boosting Photoelectrochemical Water Oxidation

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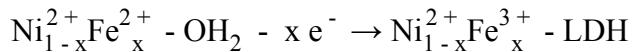
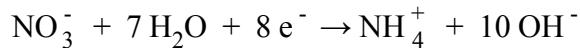
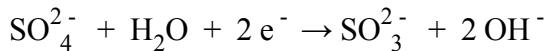
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## The Fabrication of BiVO<sub>4</sub> Seed Layer

For the fabrication of BiVO<sub>4</sub> seed layer on the fluorine doped tin oxide (FTO) coated glass substrate (<15 ohm·sq<sup>-1</sup>, 1.5 cm × 1.5 cm),<sup>1</sup> Bi(NO<sub>3</sub>)<sub>3</sub>·5H<sub>2</sub>O (5 mmol), NH<sub>4</sub>VO<sub>3</sub> (5 mmol), and citric acid (10 mmol) were dissolved in 15 mL of 20% HNO<sub>3</sub> aqueous solution and stirred for 30 min to get a transparent blue colored solution. Then, 3.75 mL acetic acid and 0.6 g polyvinyl alcohol (PVA-124, Mw~195,000) were added to the above solution and stirred vigorously until the solution became transparent. 40 μL of above solution was dropped and spin-coated twice on a pre-cleaned FTO substrate at the rotation rate of 4000 rpm for 50 s, and followed by calcined in a muffle furnace at 400 °C for 3 h.

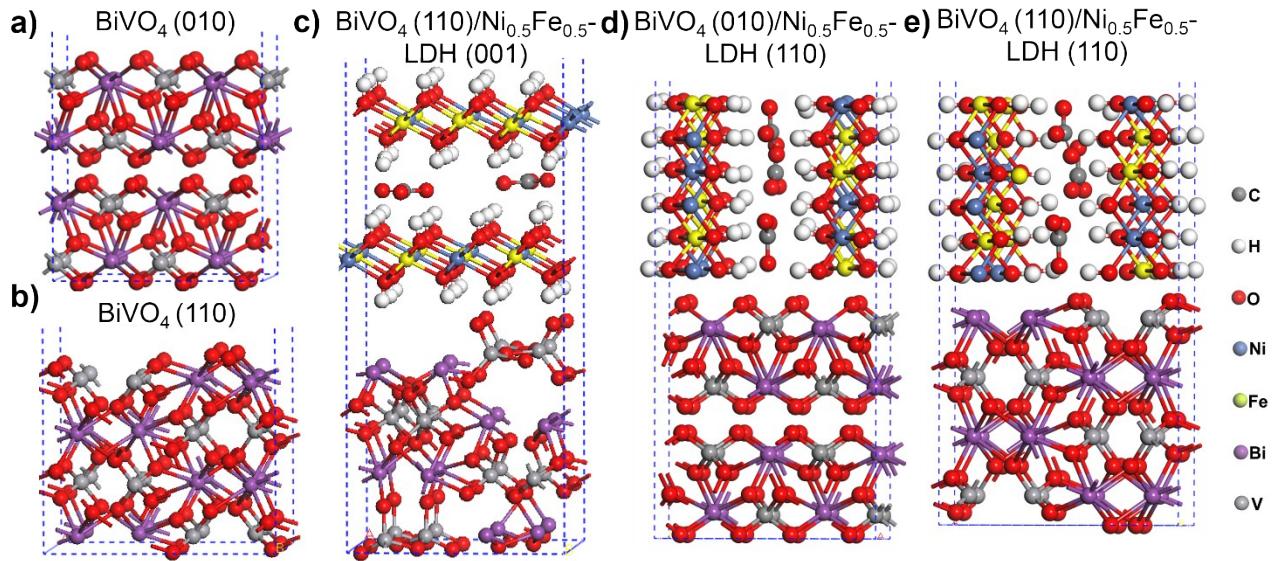
## The Formation of Fe-Based Layered Double Hydroxides (LDH)

The electrochemical reaction was controlled at -1.0 V vs. SCE, mainly involving in the reduction of sulfate ions (SO<sub>4</sub><sup>2-</sup>) and nitrate ions (NO<sub>3</sub><sup>-</sup>) at the BiVO<sub>4</sub> film surface to generate the hydroxide ions (OH<sup>-</sup>) and increase the pH value. Subsequently, the Ni<sup>2+</sup> and Fe<sup>2+</sup> ions and electro-generated OH<sup>-</sup> can easily lead to the precipitation of bimetallic hydroxide on the surface of the film.<sup>2,3</sup> After the exposure in air, Fe<sup>2+</sup> was converted to Fe<sup>3+</sup> by the self-oxidation, leading to the fabrication of Ni<sub>1-x</sub>Fe<sub>x</sub>-LDH.



The Co<sub>1-x</sub>Fe<sub>x</sub>-LDH arrays were prepared *via* the same method by replacing Ni(NO<sub>3</sub>)<sub>2</sub>·6H<sub>2</sub>O with Co(NO<sub>3</sub>)<sub>2</sub>·6H<sub>2</sub>O

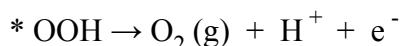
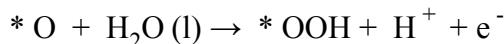
## Computational Models



**Scheme S1.** The theoretical models used in the calculations. (a)  $\text{BiVO}_4$  (010) surface, (b)  $\text{BiVO}_4$  (110) surface, (c)  $\text{BiVO}_4$  (110)/ $\text{Ni}_{0.5}\text{Fe}_{0.5}$ -LDH (001), (d)  $\text{BiVO}_4$  (010)/ $\text{Ni}_{0.5}\text{Fe}_{0.5}$ -LDH (110) and (e)  $\text{BiVO}_4$  (110)/ $\text{Ni}_{0.5}\text{Fe}_{0.5}$ -LDH (110) surface interface.

### The Theoretical Calculations of Oxygen Evolution Reaction (OER).

The water splitting reaction can be written as the Equation:  $2 \text{H}_2\text{O} (\text{l}) \rightarrow \text{O}_2 (\text{g}) + 2 \text{H}_2 (\text{g})$ . We assume that the OER is processed in the four electrons pathway, as follows:

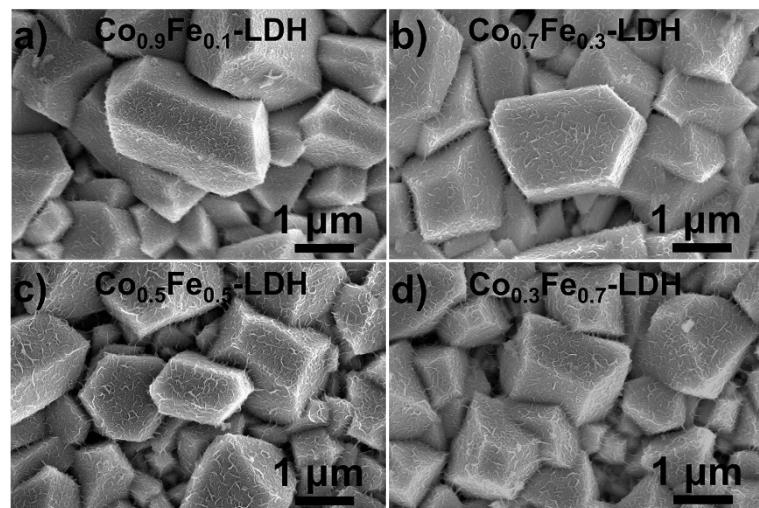


The elementary steps by which the OER occurred at neutral pH are believed to involve in the adsorbed OH and O species on the surface (\*) according to the following Equation:<sup>4,5</sup>

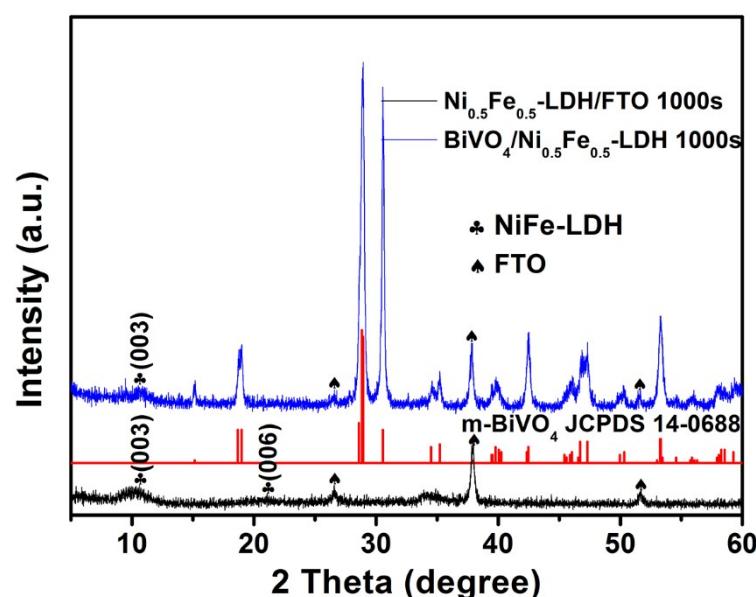
$$\Delta G = \Delta E + \Delta ZPE - T\Delta S + \Delta G_U + \Delta G_{\text{PH}}$$

Where the  $\Delta E$ ,  $\Delta ZPE$  and  $\Delta S$  represent the different intermediates energy, zero-point energy changes, and entropy of the reaction, respectively. The  $\Delta E$  is obtained from DFT calculation, while the  $\Delta ZPE$  and  $\Delta S$  are calculated from the values in previous reports.<sup>6</sup> The each step of  $\Delta G$  are obtained according to the approach by Rossmeisl et al.<sup>7</sup> The Gibbs free energies of above equation depend on the intermediates adsorption energies of \*O, \*OH and \*OOH. They are calculated relative to  $\text{H}_2\text{O}$  and  $\text{H}_2$  in the gas phase at  $U = 0.0$  V, standard conditions (1.23 V vs. RHE), and a fixed “standard” coverage of half of the adsorbate species. U is the potential measured against RHE at standard conditions ( $T = 298.15$  K,  $P = 1$  bar,  $\text{pH} = 0$ ). The theoretical overpotential is defined as: overpotential =  $\max [\Delta G_1, \Delta G_2, \Delta G_3, \Delta G_4]/e - 1.23$  V.

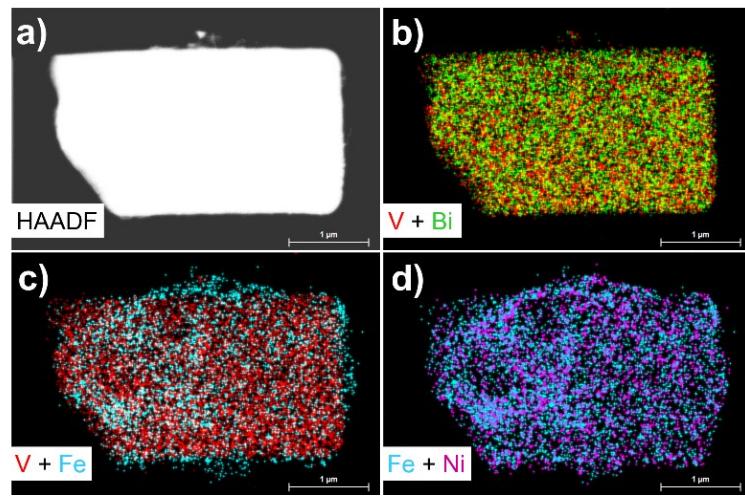
## Supporting Figures and Discussion



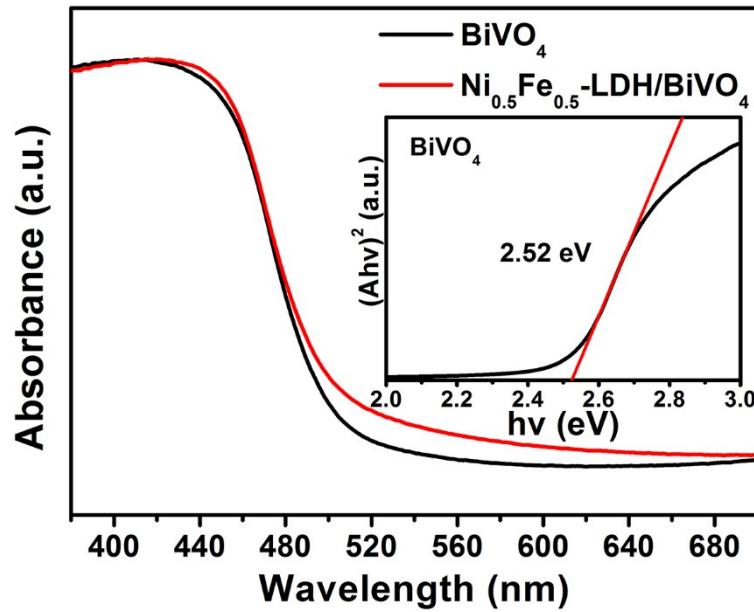
**Figure S1.** FESEM images of BiVO<sub>4</sub>/Co<sub>1-x</sub>Fe<sub>x</sub>-LDH films.



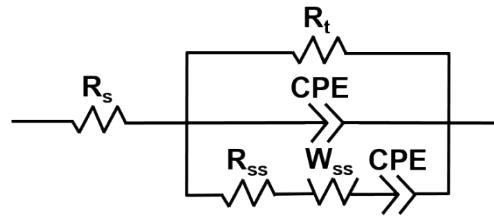
**Figure S2.** XRD patterns of Ni<sub>0.5</sub>Fe<sub>0.5</sub>-LDH film on FTO and BiVO<sub>4</sub>/Ni<sub>0.5</sub>Fe<sub>0.5</sub>-LDH film that the electrodeposition time for Ni<sub>0.5</sub>Fe<sub>0.5</sub>-LDH was 1,000 s.



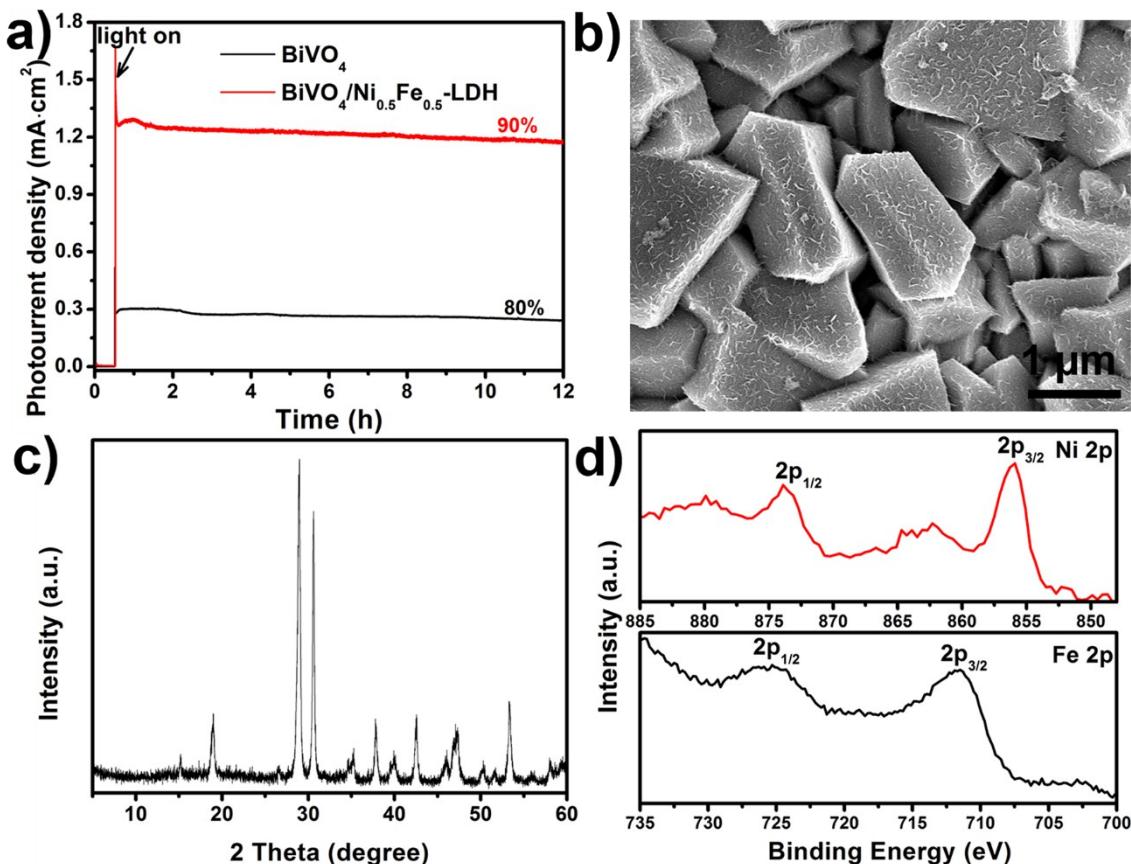
**Figures S3.** High Angle Annular Dark Field (HAADF)-STEM image and corresponding EDS mapping images of  $\text{BiVO}_4/\text{Ni}_{0.5}\text{Fe}_{0.5}\text{-LDH}$ .



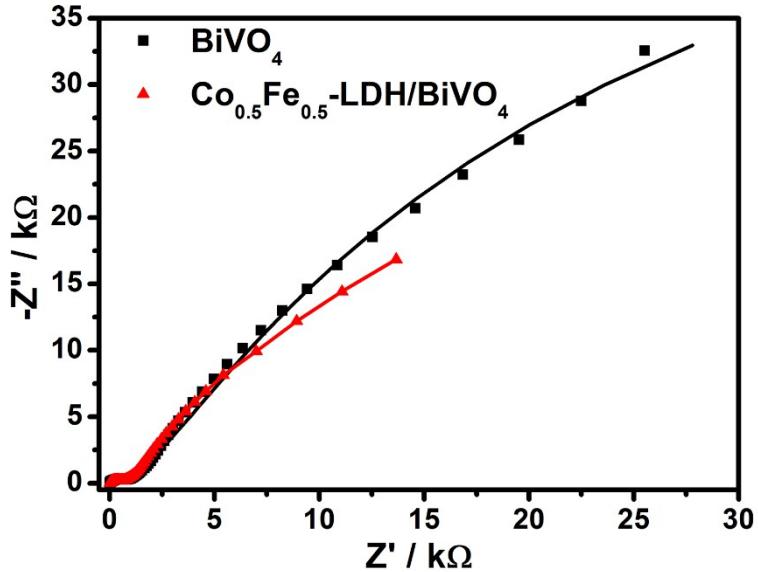
**Figure S4.** UV-vis absorbance spectra of the  $\text{BiVO}_4$  and  $\text{BiVO}_4/\text{Ni}_{0.5}\text{Fe}_{0.5}\text{-LDH}$  film.



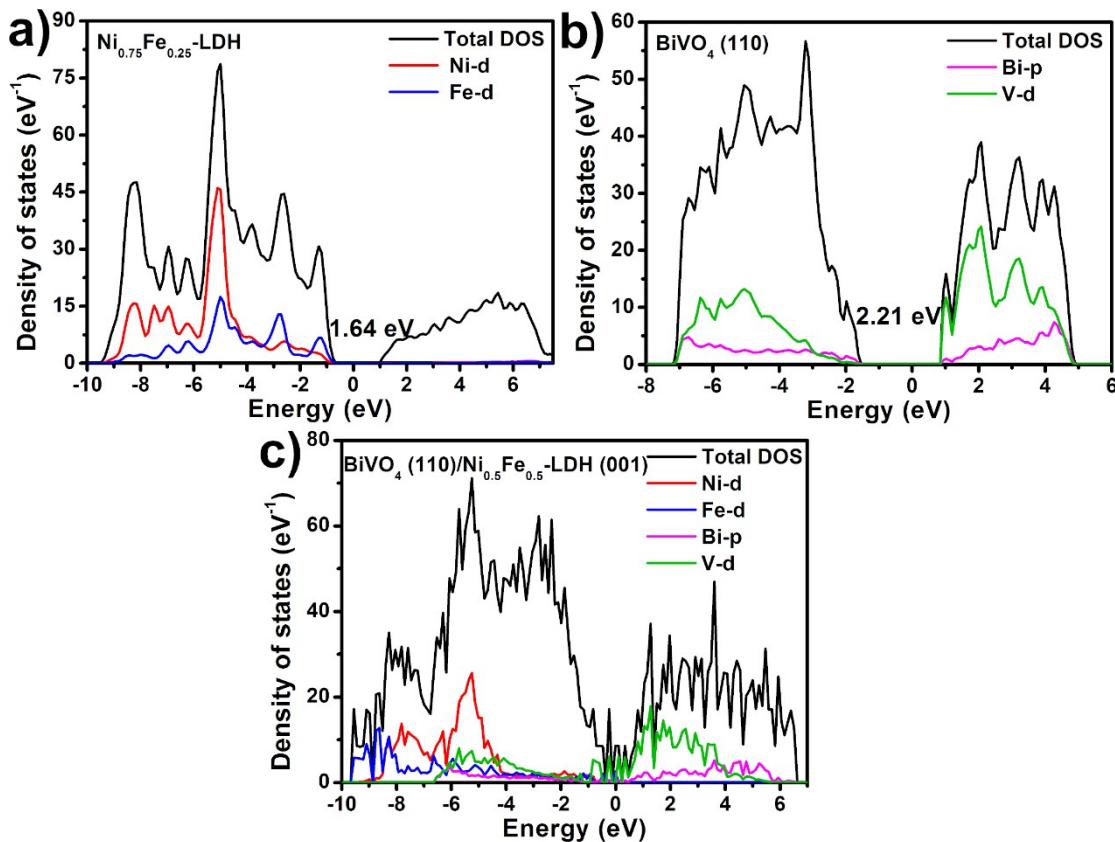
**Figure S5.** The equivalent circuit for fitting the EIS results. In the equivalent circuit,  $R_s$  is the solution resistance,  $R_t$  is the electron transfer resistance at the photoanode; CPE was constant phase angle element. The parallel disposition of the  $R_t$ -CPE circuit with ( $R_{ss}$ , CPE2 and  $W_{ss}$ ) means the band bending in the charge space layer of the photoelectrode and surface state filling occur simultaneously when the potential changes.  $R_{ss}$ , CPE2 and  $W_{ss}$  were used to describe the behaviors of the photogenerated electron-hole pairs on the interface between the photoanode and the electrolyte.  $R_{ss}$  and  $W_{ss}$  were the electron transfer resistance at the photoanode/electrolyte interface and the Warburg resistance caused by some delay in the surface states response.<sup>8,9</sup>



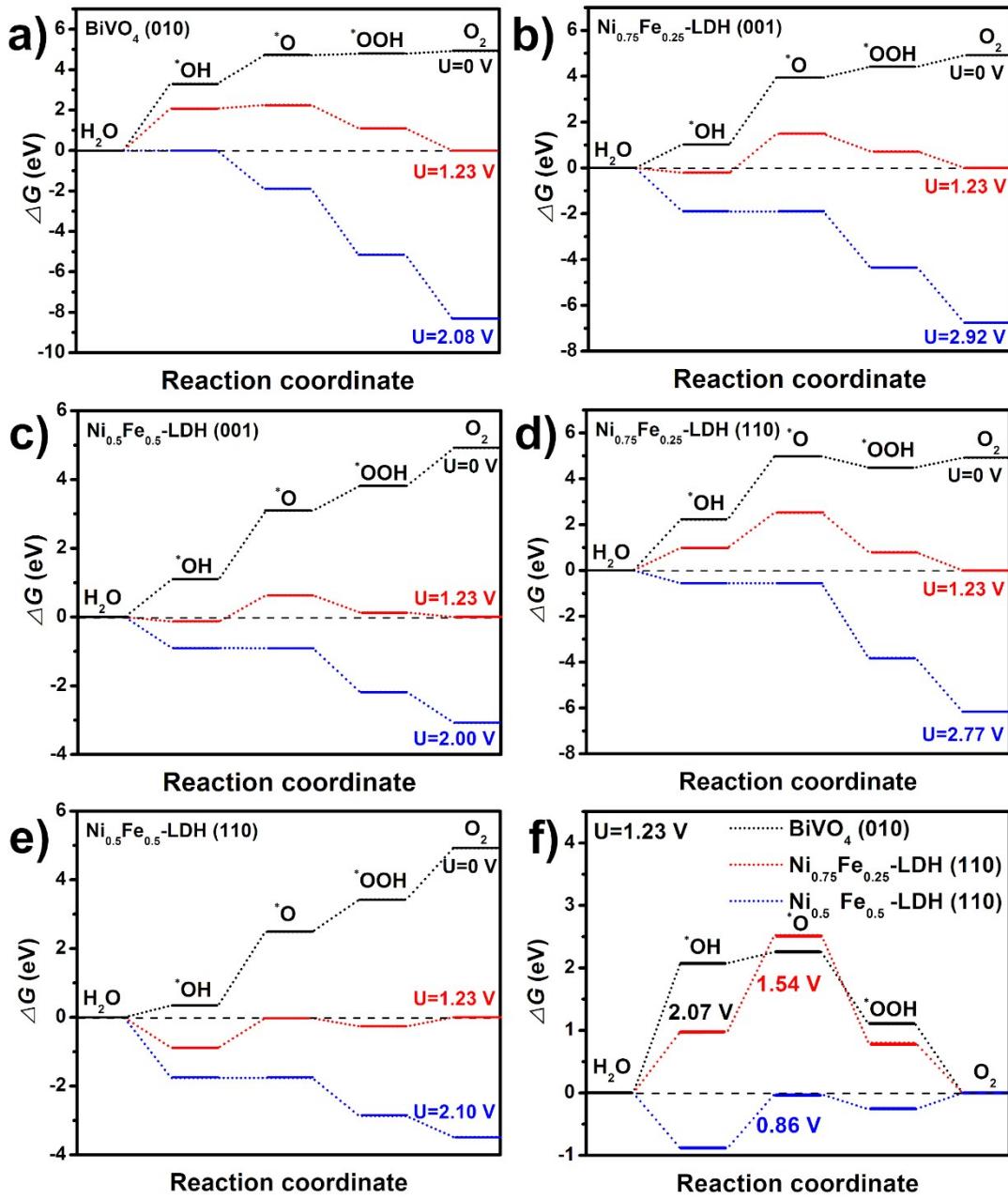
**Figures S6.** (a) Stability for  $\text{BiVO}_4$  and  $\text{BiVO}_4/\text{Ni}_{0.5}\text{Fe}_{0.5}\text{-LDH}$  photoanodes under continuous illumination at 1.23 V *vs.* RHE for 12 h. (b) SEM image, (c) XRD pattern and (d) high resolution XPS spectra of Ni 2p and Fe 2p for the  $\text{BiVO}_4/\text{Ni}_{0.5}\text{Fe}_{0.5}\text{-LDH}$  film after continuous illumination at 1.23 V *vs.* RHE for 12 h.



**Figures S7.** Nyquist plots of the EIS measured at the open circuit potential for the BiVO<sub>4</sub> and BiVO<sub>4</sub>/Co<sub>0.5</sub>Fe<sub>0.5</sub>-LDH photoanodes under AM 1.5G (100 mW/cm<sup>2</sup>) illumination.



**Figure S8.** The density of states (DOS) of (a) Ni<sub>0.75</sub>Fe<sub>0.25</sub>-LDH surface model, (b) BiVO<sub>4</sub> (110) surface model, and (c) BiVO<sub>4</sub> (110)/Ni<sub>0.5</sub>Fe<sub>0.5</sub>-LDH interface model.



**Figure S9.** Standard Gibbs free energy diagrams for OER over (a) BiVO<sub>4</sub> (010) surface, (b) Ni<sub>0.75</sub>Fe<sub>0.25</sub>-LDH (001) surface, (c) Ni<sub>0.5</sub>Fe<sub>0.5</sub>-LDH (001) surface, (d) Ni<sub>0.75</sub>Fe<sub>0.25</sub>-LDH (110) surface and (e) Ni<sub>0.5</sub>Fe<sub>0.5</sub>-LDH (110) surface. (f) The OER at U=1.23 V over LDH (110) surface. The rate-determining steps for BiVO<sub>4</sub> and NiFe-LDH are the oxidation of H<sub>2</sub>O to \*OH and \*OH to \*O, respectively. Therefore, the overpotentials for BiVO<sub>4</sub> and NiFe-LDH are calculated from  $\Delta G_1$  and  $\Delta G_2$ , respectively.

**Table S1.** Comparison table for the LDH/photoelectrode composites for PEC water oxidation under AM 1.5G ( $100 \text{ mW}\cdot\text{cm}^{-2}$ ) illumination.

Composites	Deposition method	Deposition time	$\Delta E_{\text{onset}}^1$ (mV)	Enhancement factor <sup>2</sup>	Reference
ZnO@CoNi-LDH	electrodeposition	100 s	150	3.0	10
NiFe-LDH/Ta <sub>3</sub> N <sub>5</sub>	solvothermal	17 h	100	2.0	11
$\alpha$ -Fe <sub>2</sub> O <sub>3</sub> /Zn-Co LDH	electrodeposition	60 s	-	1.4	12
Mn:Fe <sub>2</sub> O <sub>3</sub> /NiFe-LDH	hydrothermal	6 h	200	1.3	13
TiO <sub>2</sub> /rGO/NiFe-LDH	electrodeposition	50 s	-	1.3	14
TiO <sub>2</sub> @CoNi-LDHs	electrodeposition	30 s	-	3.3	15
TiO <sub>2</sub> /ZnFe-LDH	photo-assisted electrodeposition	50 s	-	1.9	16
WO <sub>3</sub> @NiFe-LDH	electrodeposition	200 s	60	1.4	17
CoAl-LDH@BiVO <sub>4</sub>	hydrothermal	4 h	540	2.0	18
BiVO <sub>4</sub> /CoLa-LDH	electrodeposition	20 s	530	2.0	19
CdTe@LDH@BiVO <sub>4</sub>	hydrothermal	15 h	-	1.1	20
BiVO <sub>4</sub> /NiFe-LDH	electrodeposition	20 s	320	4.0	This work

1. Cathodic shift of the onset potential ( $E_{\text{onset}}$ ) of water oxidation photocurrent after the LDH deposition.

2. Increase of water oxidation photocurrent at 1.23 V vs. RHE after the LDH deposition.

**Table S2.** Fitted parameters of the EIS plots of BiVO<sub>4</sub>, BiVO<sub>4</sub>/Ni<sub>0.5</sub>Fe<sub>0.5</sub>-LDH and BiVO<sub>4</sub>/Co<sub>0.5</sub>Fe<sub>0.5</sub>-LDH interface nanostructure photoanodes in 0.5 M Na<sub>2</sub>SO<sub>4</sub> solution.

Sample	R <sub>s</sub> ( $\Omega\cdot\text{cm}^2$ )	R <sub>t</sub> ( $\Omega\cdot\text{cm}^2$ )	R <sub>ss</sub> ( $\text{k}\Omega\cdot\text{cm}^2$ )
BiVO <sub>4</sub>	13.66	690.3	108.2
BiVO <sub>4</sub> /Ni <sub>0.5</sub> Fe <sub>0.5</sub> -LDH	13.31	571.2	40.87
BiVO <sub>4</sub> /Co <sub>0.5</sub> Fe <sub>0.5</sub> -LDH	13.50	610.5	58.46

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